

Electronic Patent Application Fee Transmittal

Application Number:	10802150			
Filing Date:	17-Mar-2004			
Title of Invention:	Etching process including plasma pretreatment for generating fluorine-free carbon-containing polymer on a photoresist pattern			
First Named Inventor/Applicant Name:	Keun-Hee Bai			
Filer:	Frank Chau/Jaewoo Park			
Attorney Docket Number:	8021-215 (SS-19582-US)			
Filed as Large Entity				
Utility Filing Fees				
Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
Basic Filing:				
Pages:				
Claims:				
Miscellaneous-Filing:				
Petition:				
Patent-Appeals-and-Interference:				
Filing a brief in support of an appeal	1402	1	510	510
Post-Allowance-and-Post-Issuance:				
Extension-of-Time:				

Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
Miscellaneous:				
Total in USD (\$)				510